

S/N: 09/047,944

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Moshe Finarov

Examiner: E. Morgan

Serial No: 09/047,944

Group Art Unit: 3723

Filed: March 25, 1998

Attorney Docket No: M-3417-1C US
(P-743-US1)

Title: APPARATUS FOR OPTICAL INSPECTION OF WAFERS DURING
POLISHING

San Jose, California
November 2, 1998

AMENDMENT AND INTERVIEW SUMMARY

Commissioner for Patents and Trademarks
Washington, DC 20231

Sir:

This paper is submitted in response to the First Official Action of June 1, 1998.

Please amend the Patent Application as follows.

IN THE SPECIFICATION:

At page 8, line 17, delete "14" and replace it with - -13- -.

IN THE DRAWINGS:

Please amend Fig. 13, submitted herewith.

IN THE CLAIMS:

Please amend claims 17-19 as below.

17. (Once Amended). A [polisher having the ability to measure the thickness of a top layer of a wafer, the polisher] wafer polishing apparatus comprising: